

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Wunnicke, <i>et al.</i>	Docket No.:	INF 2004 SP 00138 US
Serial No.:	10/781,920	Art Unit:	1756
Filed:	February 20, 2004	Examiner:	Brittany L. Raymond
For:	Method for Fabricating a Resist Mask for Patterning Semiconductor Substrates		

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Dear Sir:

The following amendments and remarks are presented in response to the Examiner's
Office Action mailed August 1, 2007. Please amend the above-referenced application as follows.